

REMARKS

With respect to the Office Action dated May 9, 2005, Applicant notes with appreciation that claims 16-20 were allowed and that claims 3-5 and 11-13 were objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.

In response, Applicant has amended the independent claim 1 to include the indicated allowable subject matter of "*wherein the increased gate-to-drain etch recess spacing is at least four microns,*" as recited in the original dependent claim 3. Similarly, the independent claim 9 has been amended to include the indicated allowable subject matter of "*creating the increased gate-to-drain etch recess spacing of at least four microns,*" as recited in the original dependent claim 11. As a result, claims 3 and 11 have been canceled. In addition, Applicant has rewritten the "objected to" claim 12 in independent form by adding a new independent claim 21. Applicant has also added a new dependent claim 22, which includes the subject matter of the "objected to" claim 13. Therefore, Applicant respectfully requests that claims 1, 9, 21 and 22 be allowed.

With respect to the dependent claims 2, 4-8, 10 and 12-15, each of these dependent claims depends on one of the amended independent claims 1 and 9. As such, these dependent claims include all the limitations of their respective base claims. Therefore, Applicant submits that these dependent claims are allowable for at least the same reasons as their respective base claims.

Applicant respectfully requests a notice of allowance in view of the claim amendments and the remarks made herein.

Respectfully submitted,
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